NOTES:

1. SUBSTRATE:
   FUSED SILICA

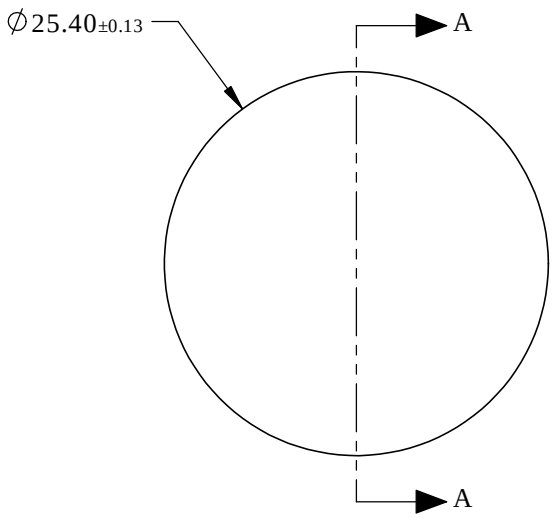
2. SURFACE S1 TO BE PARALLEL TO SURFACE S2 TO WITHIN <1 ARC MIN

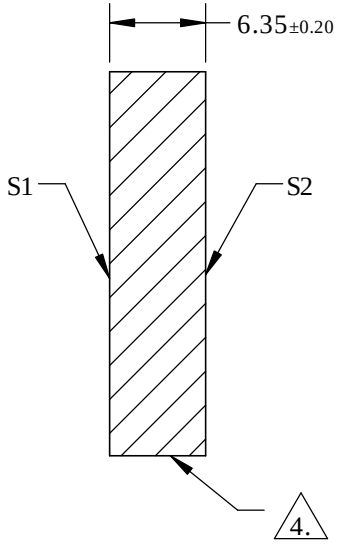
3. COATING (APPLY ACROSS CLEAR APERTURE)
   S1: CENTER ENERGY/WAVELENGTH: 65eV/19nm
   BANDWIDTH: 6eV/1.8nm
   REFLECTIVITY: Rs > 38% @ 65eV/19nm, 5° AOI
   SUPPORTED PULSE DURATION: 330 attoseconds

   S2: NONE

4. FINE GRIND SURFACE

5. RoHS: COMPLIANT





SECTION A-A

FOR INFORMATION ONLY:
DO NOT MANUFACTURE
PARTS TO THIS DRAWING

SPECIFICATIONS SUBJECT TO CHANGE WITHOUT NOTICE
DIMENSIONS ARE FOR REFERENCE ONLY

	S1	S2
SHAPE	PLANO	PLANO
SURFACE FLATNESS	λ/10 @ 632.8nm	N/A
SURFACE ROUGHNESS	<1Å	N/A
CLEAR APERTURE	∅20.32	N/A
BEVEL	PROTECTIVE AS NEEDED	PROTECTIVE AS NEEDED

THIRD ANGLE PROJECTION

ALL DIMS IN mm

Edmund Optics®

TITLE: 25.4mm Dia., 19nm (65eV), 5° EUV/XUV Attosecond Multilayer Flat Mirror

DWG NO: 16765

SHEET 1 OF 1